

*Euter
Amendment
After
Final
AM
3-12-04*

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Client/Matter: 081468-0305843

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Previously presented) A lithographic projection apparatus, comprising:
 - a first substrate table configured to hold a first substrate;
 - a second substrate table configured to hold a second substrate;
 - a first station at which measurement of the first and second substrates may be performed;
 - a second station at which the first and second substrates may be exposed;
 - a displacement measuring system configured to measure displacements of the first and second substrate tables in the first and second stations;
 - a planar motor configured to independently transfer the first and second substrate tables between the first and the second stations;
 - a radiation system, associated with the second station, configured to provide a beam of radiation;
 - a support configured to support a patterning device, the patterning device configured to pattern the beam according to a desired pattern; and
 - a projection system configured to project the patterned beam onto a target portion of the first and second substrates when the first and second substrates are at the second station, respectively, wherein the displacement measuring system is configured to continuously measure displacements of the first and second substrate tables in at least two directions during transfer between the first and second stations.

2. (Cancelled)

3. (Previously presented) A lithographic projection apparatus according to claim 1, further comprising:
 - a first measurement system in the first station configured to measure first relative positions of the first and second substrates to the first and second substrate tables, respectively;